

AMENDMENTS TO THE CLAIMS

1.- 2. (Canceled).

3. (Currently Amended) A substrate cleaning device according to ~~claim 1~~,
~~wherein comprising:~~

a first cleaning room including a first cleaning portion for cleaning a substrate placed therein; and

a second cleaning room including a second cleaning portion for cleaning a substrate provided therein,

wherein the first cleaning room is stacked on the second cleaning room so that at least a portion of the first cleaning room overlaps at least a portion of the second cleaning room, wherein

a first table is provided in the first cleaning room, and the first table is slid along a first ball screw by rotating the first ball screw, with the substrate placed in the first cleaning room being placed on the first table; and

a second table is provided in the second cleaning room, and the second table is slid along a second ball screw by rotating the second ball screw, with the substrate placed in the second cleaning room being placed on the second table.

4. – 5. (Canceled).

6. (Currently Amended) A substrate cleaning device ~~according to claim 5~~,
~~wherein comprising:~~

a first cleaning room including a first cleaning portion for cleaning a substrate placed therein; and

a second cleaning room including a second cleaning portion for cleaning a substrate provided therein,

wherein the first cleaning room is stacked on the second cleaning room so that at least a portion of the first cleaning room overlaps at least a portion of the second cleaning room,

a first opening portion is provided on a side wall of the first cleaning room,
a second opening portion is provided on a side wall of the second cleaning room, and
the side wall of the first cleaning room provided with the first opening portion is opposite
to the side wall of the second cleaning room provided with the second opening portion.

7. (Currently Amended) A substrate cleaning device ~~according to claim 1,~~
~~wherein~~comprising:
a first cleaning room including a first cleaning portion for cleaning a substrate placed
therein; and
a second cleaning room including a second cleaning portion for cleaning a substrate
provided therein,
wherein the first cleaning room is stacked on the second cleaning room so that at least a
portion of the first cleaning room overlaps at least a portion of the second cleaning room,
wherein
the first cleaning portion comprises a first nozzle head having a first blowing portion for
blowing gas onto the substrate placed in the first cleaning room and a first suctioning portion for
suctioning the gas in the first cleaning room; and
the second cleaning portion comprises a second nozzle head having a second blowing
portion for blowing gas onto the substrate placed in the second cleaning room and a second
suctioning portion for suctioning the gas in the second cleaning room.

8. – 9. (Canceled).

10. (Currently Amended) A substrate processing facility ~~according to claim 9,~~
~~wherein~~comprising a clean room, wherein:
a substrate cleaning device is provided in the clean room; and
the substrate cleaning device comprises:
a first cleaning room including a first cleaning portion for cleaning a substrate
placed

therein; and

a second cleaning room including a second cleaning portion for cleaning a substrate provided therein,

wherein the first cleaning room is stacked on the second cleaning room so that at least a portion of the first cleaning room overlaps at least a portion of the second cleaning room,

a first table is provided in the first cleaning room, and the first table is slid along a first ball screw by rotating the first ball screw, with the substrate placed in the first cleaning room being placed on the first table; and

a second table is provided in the second cleaning room, and the second table is slid along a second ball screw by rotating the second ball screw, with the substrate placed in the second cleaning room being placed on the second table.

11. (Original) A substrate processing facility according to claim 10, wherein a first loading apparatus for placing the substrate on the first table in the first cleaning room and a second loading apparatus for placing the substrate on the second table in the second cleaning room are provided in the clean room.

12. (Original) A substrate processing facility according to claim 10, wherein the first loading apparatus and the second loading apparatus are arranged substantially on a line with the substrate cleaning device being sandwiched between the first loading apparatus and the second loading apparatus in the clean room.